

APPROVED	O.G. FIG. 2
BY	CLASS. SUB. 35.00
DRAFTSMAN	438 706

TITLE: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON
SUBSTRATE DURING GATE STACK ETCH
Inventor: Pan et al.
Serial No.: 09/614,113
Docket No.: 2269-2915.3US

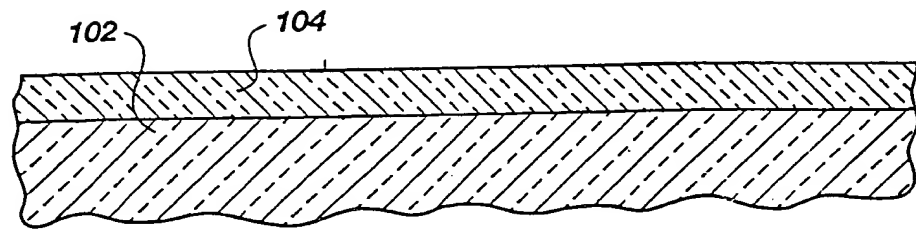


Fig. 1

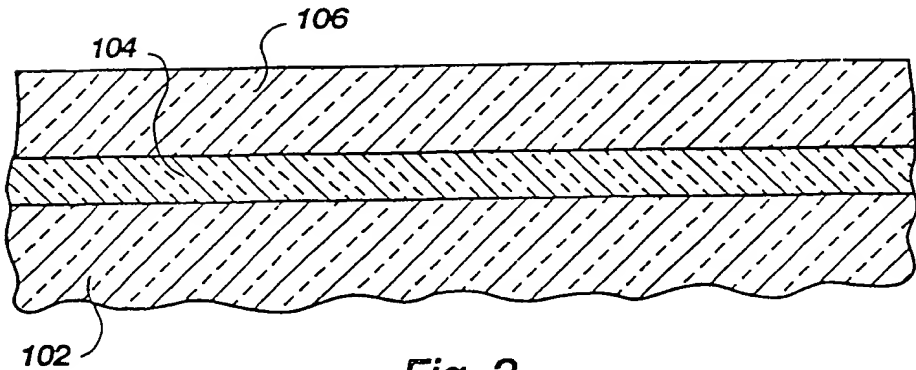


Fig. 2

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TITLE: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON
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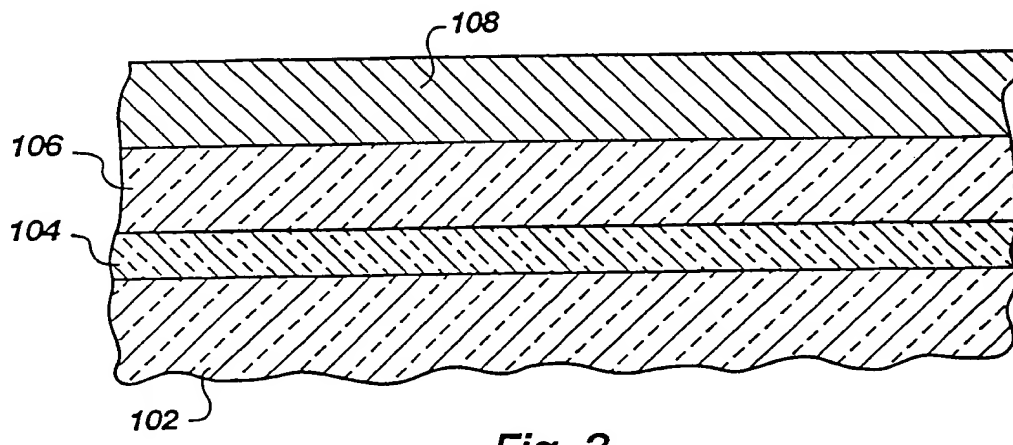


Fig. 3

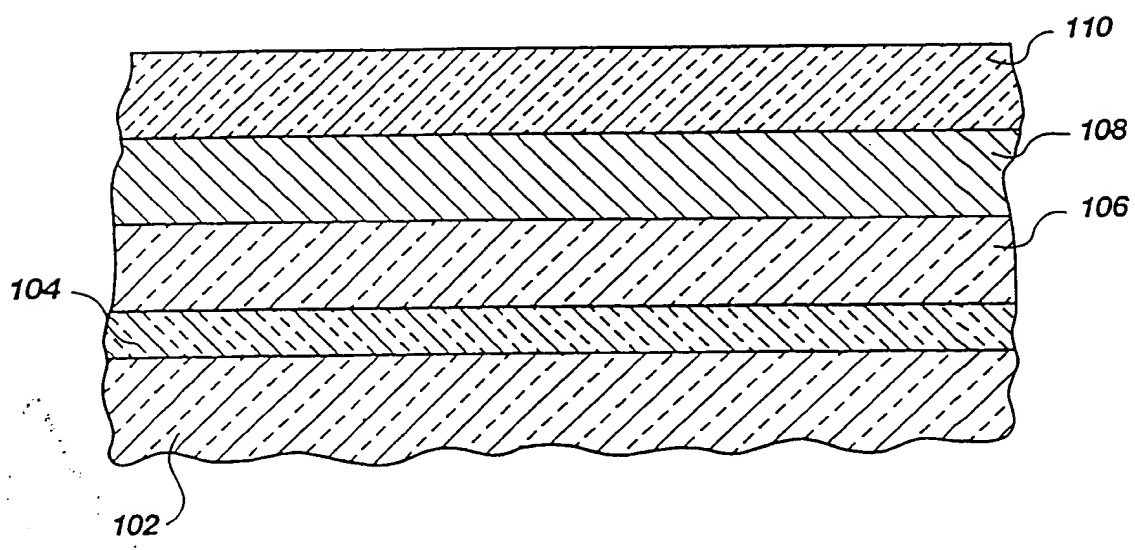


Fig. 4

APPROVED	O.G. FIG. 6	
BY	CLASS	SUBCLASS
DRAFTSMAN	438	708

TITLE: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON
SUBSTRATE DURING GATE STACK E
Inventor: Pan et al.
Serial No.: 09/614,113
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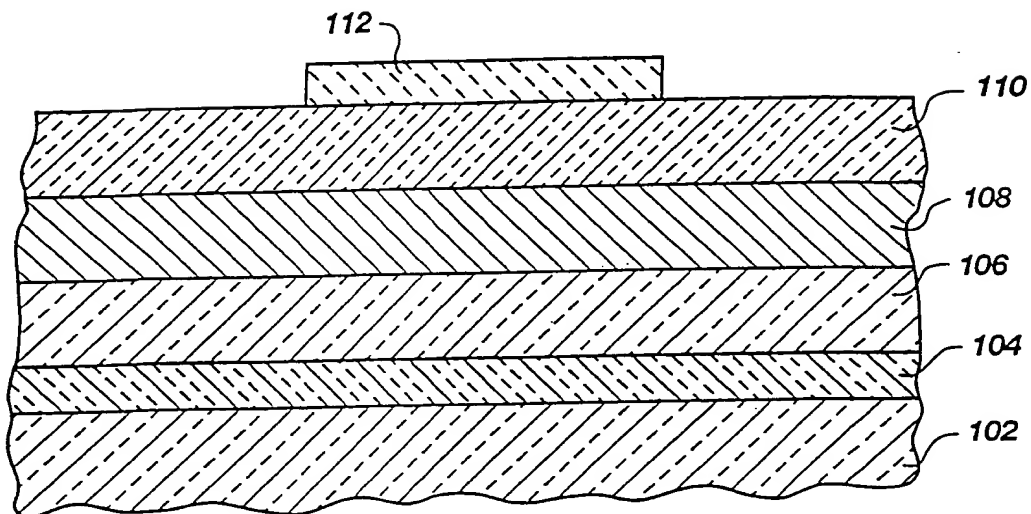


Fig. 5

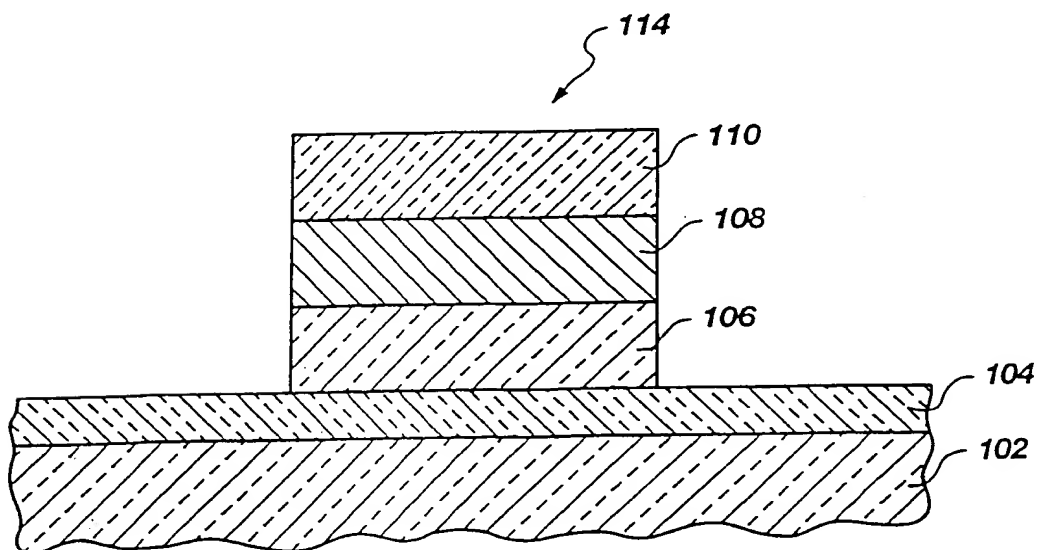
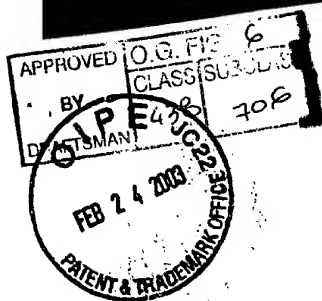


Fig. 6

(24)



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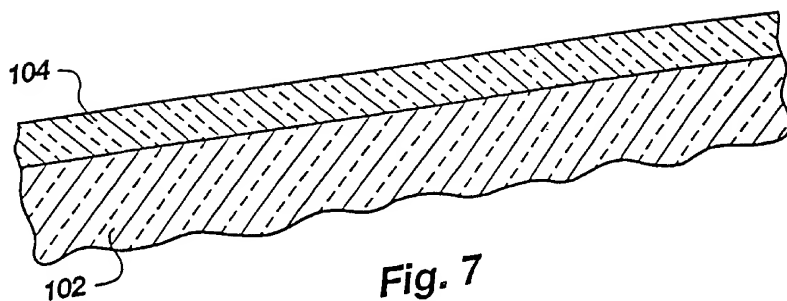


Fig. 7

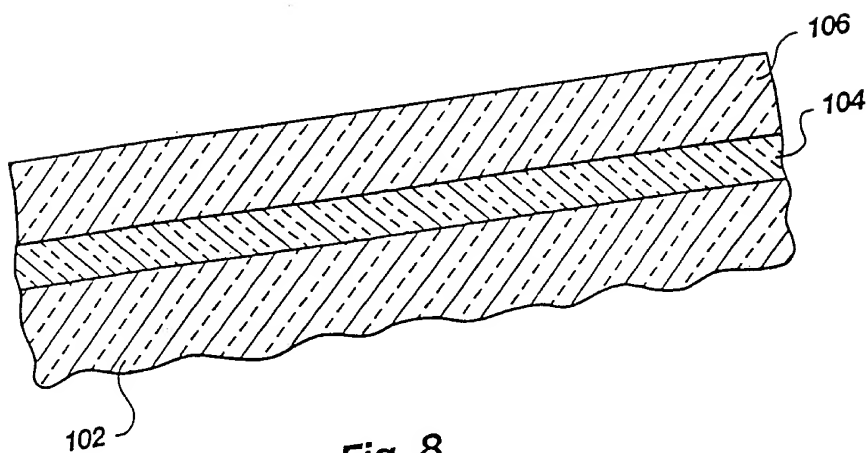


Fig. 8

APPROVED	O.G. FIG. 6
BY	CLASS
DRAFTSMAN	SUBCL/SS
438	708

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Serial No.: 09/614,113
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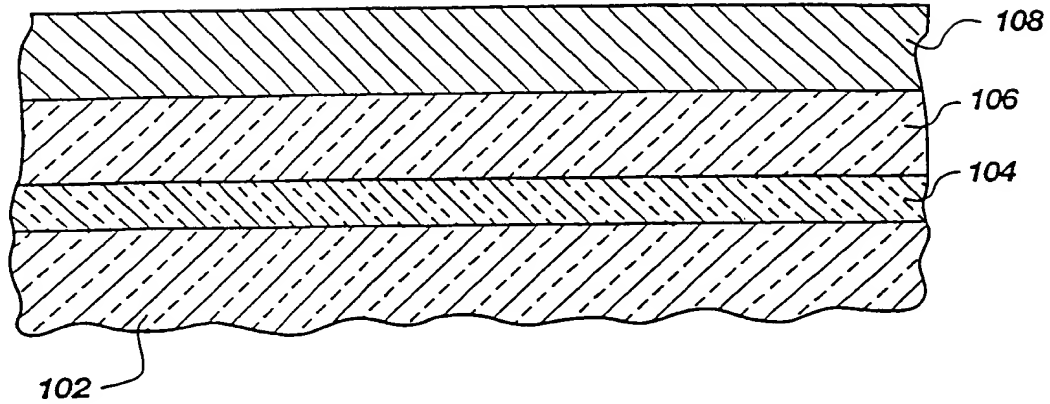
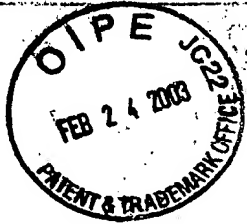


Fig. 9

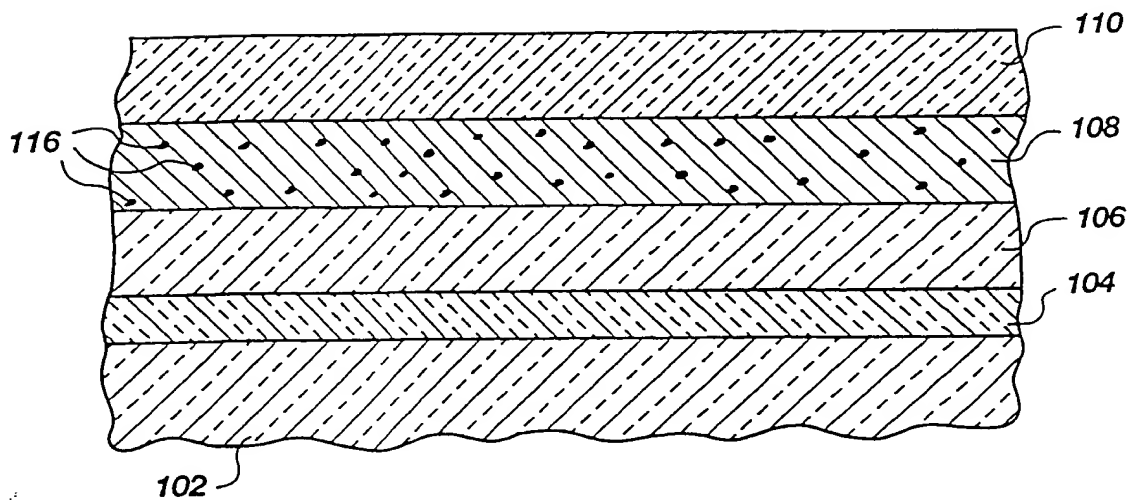


Fig. 10

APPROVED	O.G. FIG. 6
BY	CLASS. SUBCLASS
DRAFTSMAN	438 706

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SUBSTRATE DURING GATE STACK E
Inventor: Pan et al.
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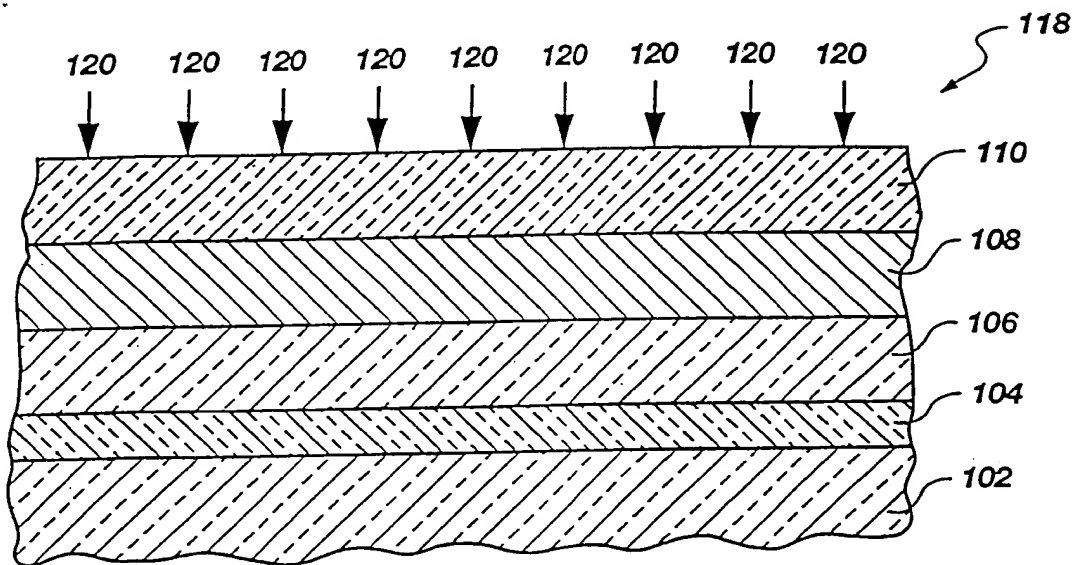


Fig. 11

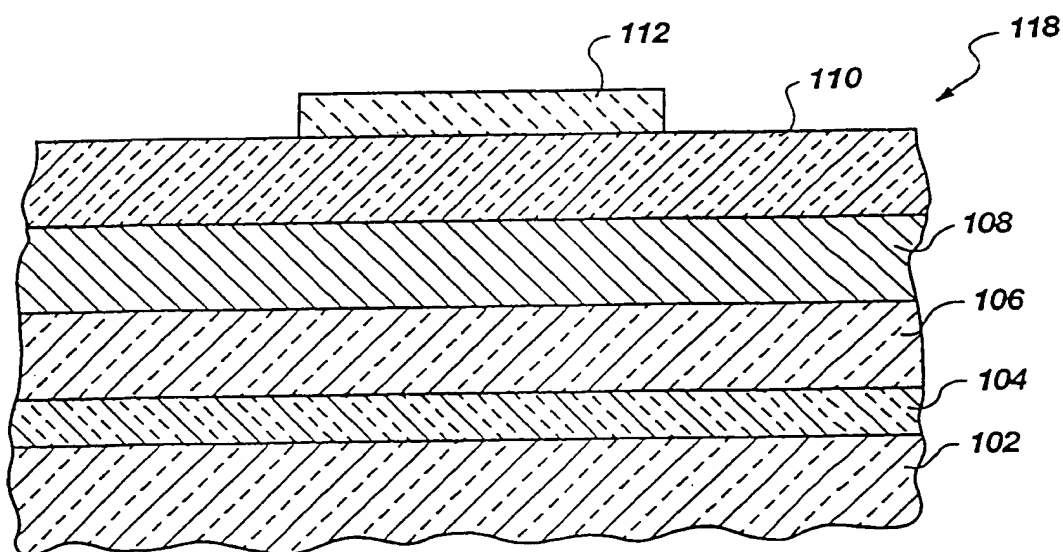
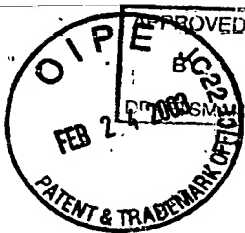


Fig. 12



APPROVED	
O.G. FIG.	7
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438	706

TITLE: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON SUBSTRATE DURING GATE STACK

Inventor: Pan et al.
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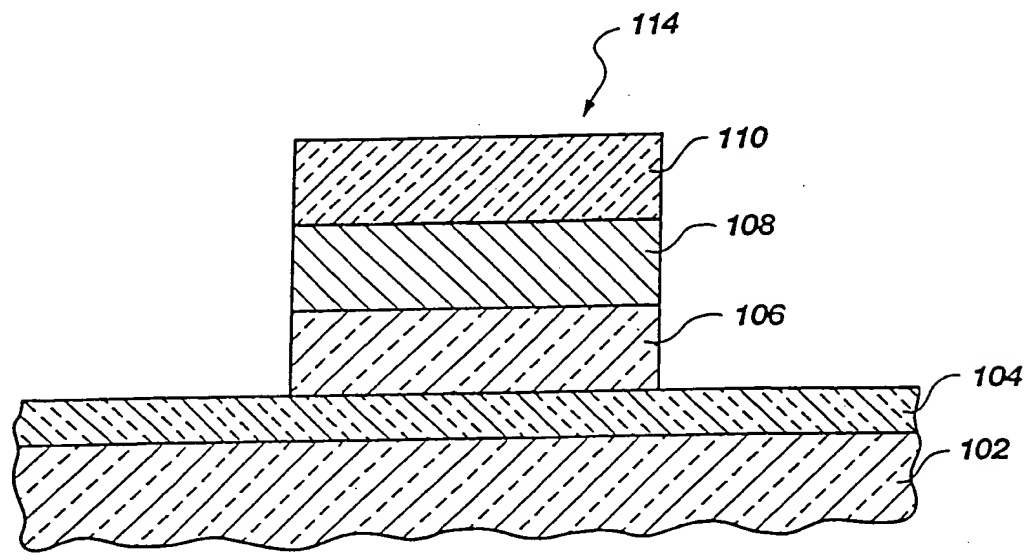


Fig. 13

APPROVED	O.G. FILE 6
BY	CLASS/SUBCLAS
DRAFTSMAN	438 706

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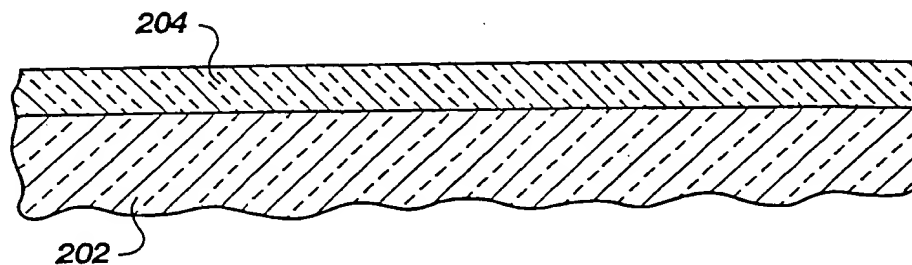


Fig. 14
(PRIOR ART)

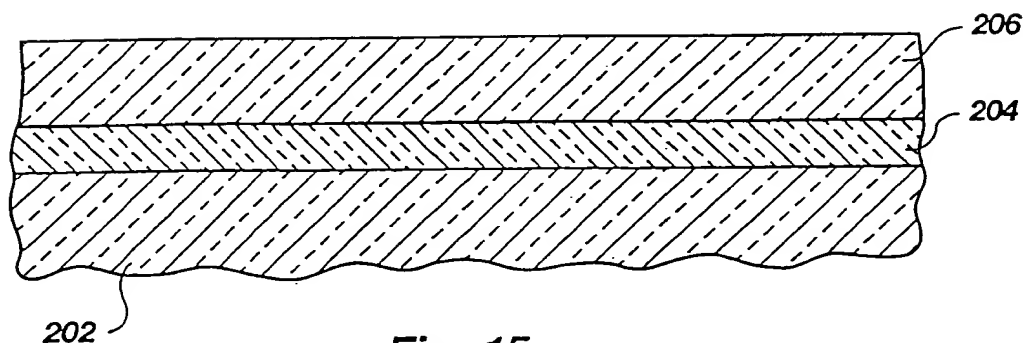
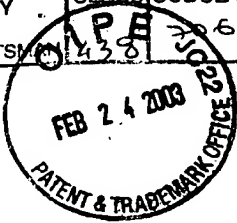


Fig. 15
(PRIOR ART)

APPROVED	O.G. FIG. 6
BY	CLASS. SUBCLAS.
DRAFTSMAN	438 306

TITLE: TECHNIQUE FOR ELIMINATION OF PITTING ON SILICON
SUBSTRATE DURING GATE STACK ETC
Inventor: Pan et al.
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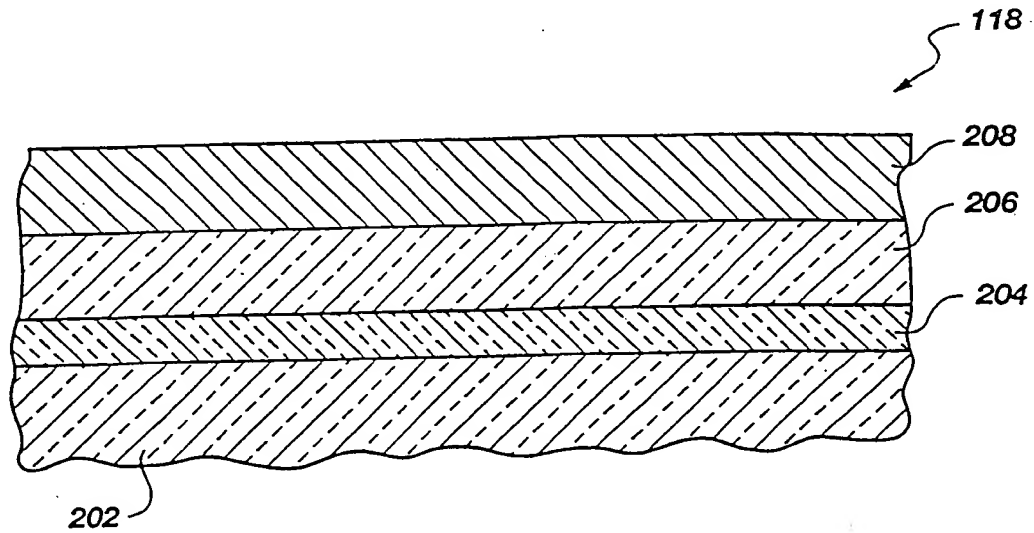


Fig. 16
(PRIOR ART)

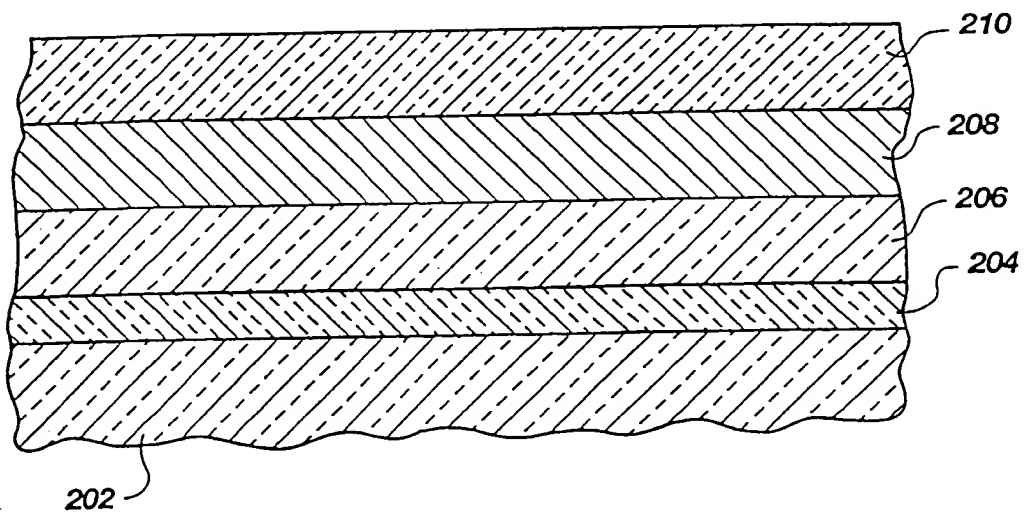
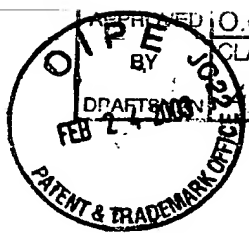


Fig. 17
(PRIOR ART)



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38 706

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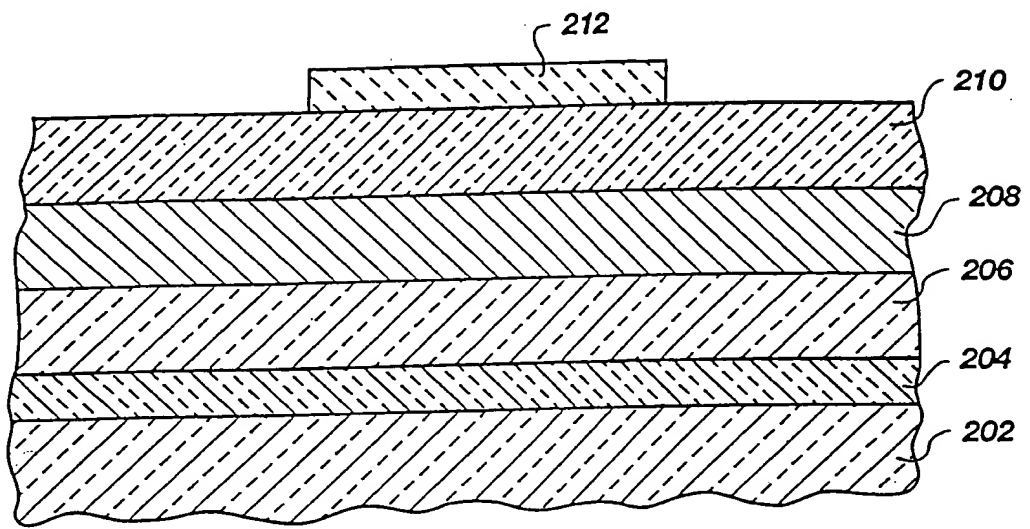


Fig. 18
(PRIOR ART)

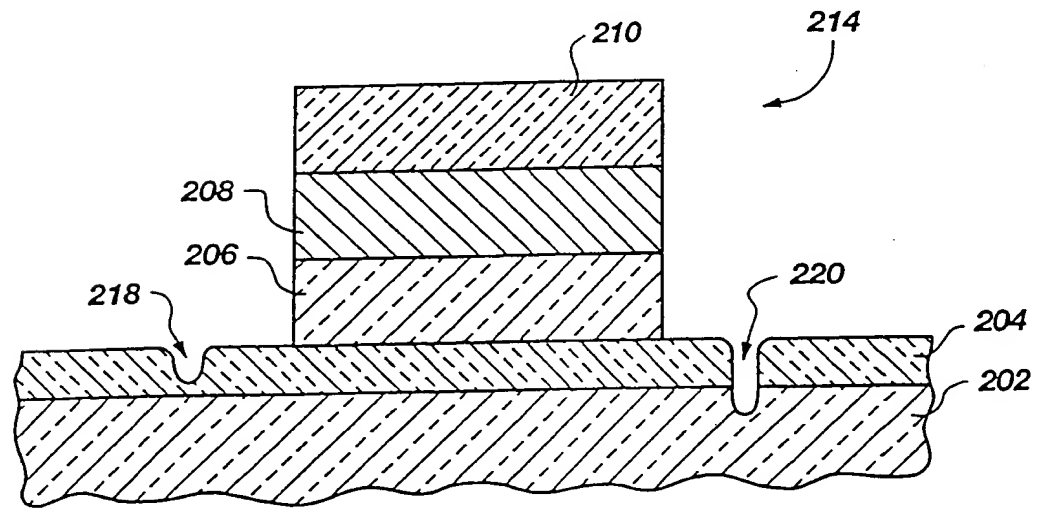


Fig. 19
(PRIOR ART)

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Inventor: Pan et al.
Serial No.: 09/614,113
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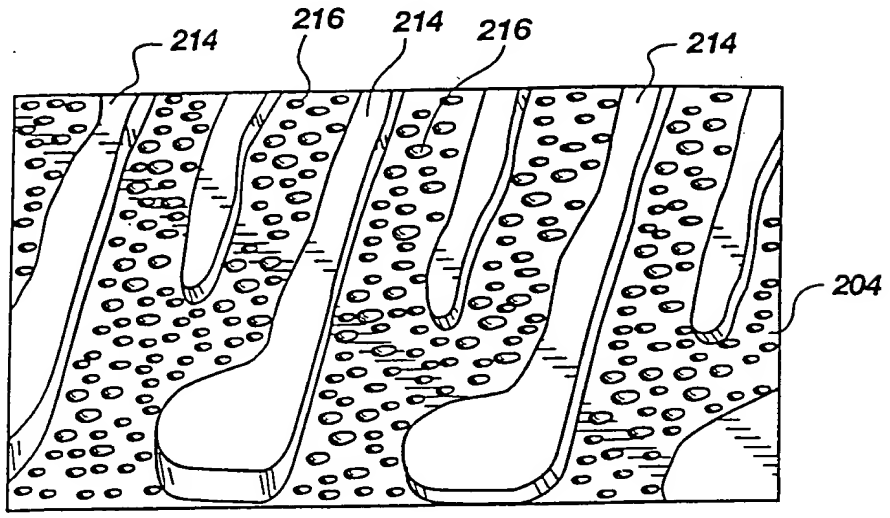


Fig. 20
(PRIOR ART)

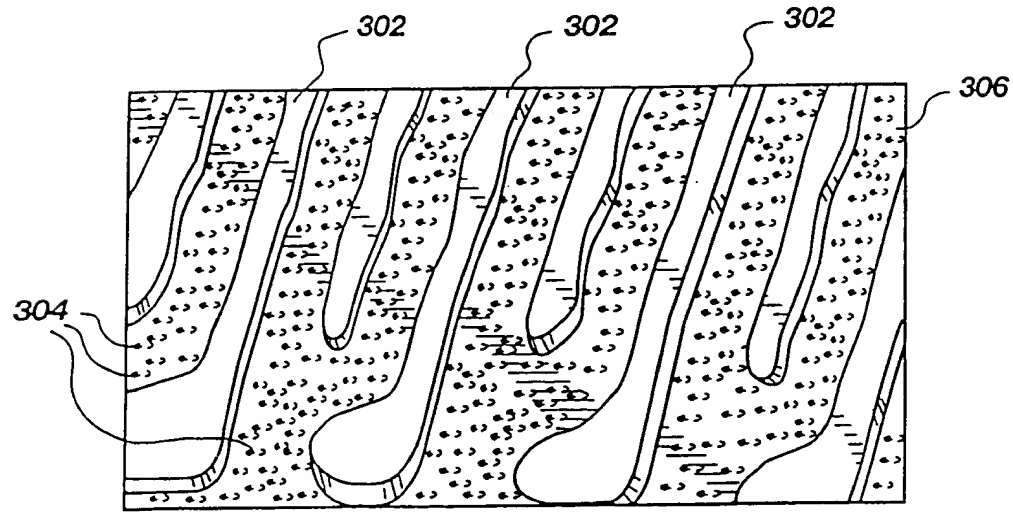


Fig. 21
(PRIOR ART)

APPROVED	O.G. FIG. 8
BY	CLASS SUBCLAS
DRAFT	138 706

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Inventor: Pan et al.
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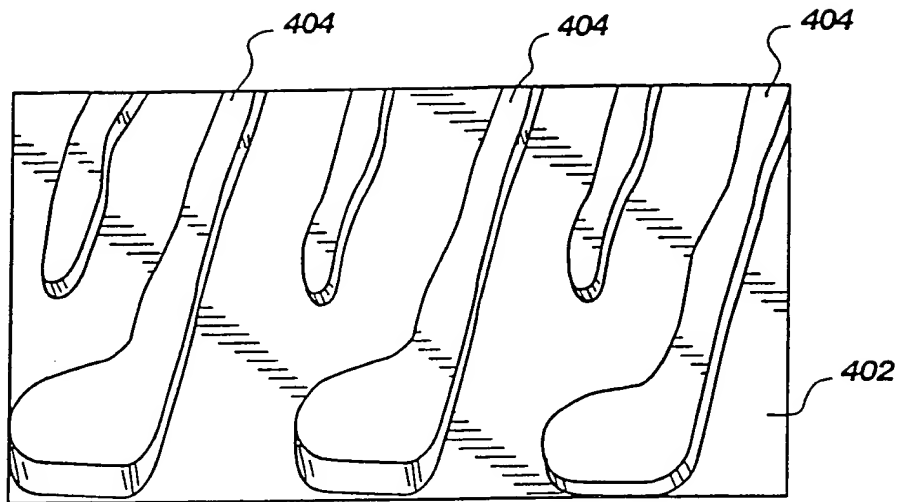


Fig. 22

APPROVED	O.G. FIG. 6	
BY	CLASS	SUBCLASS
DRAFTSMAN	438	706

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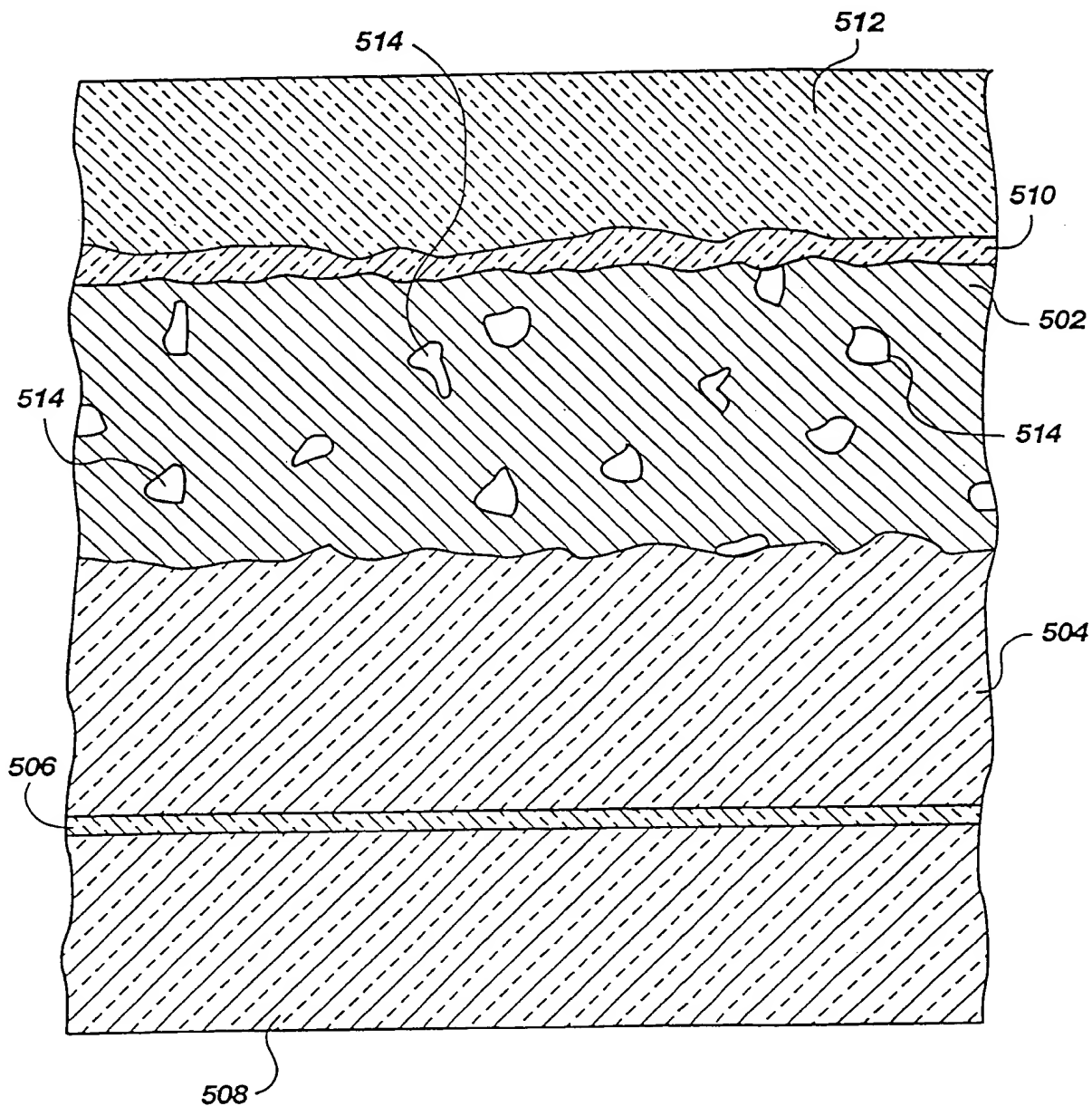


Fig. 23
(PRIOR ART)

APPROVED	U.G. FIG.	6
BY	CLASS	
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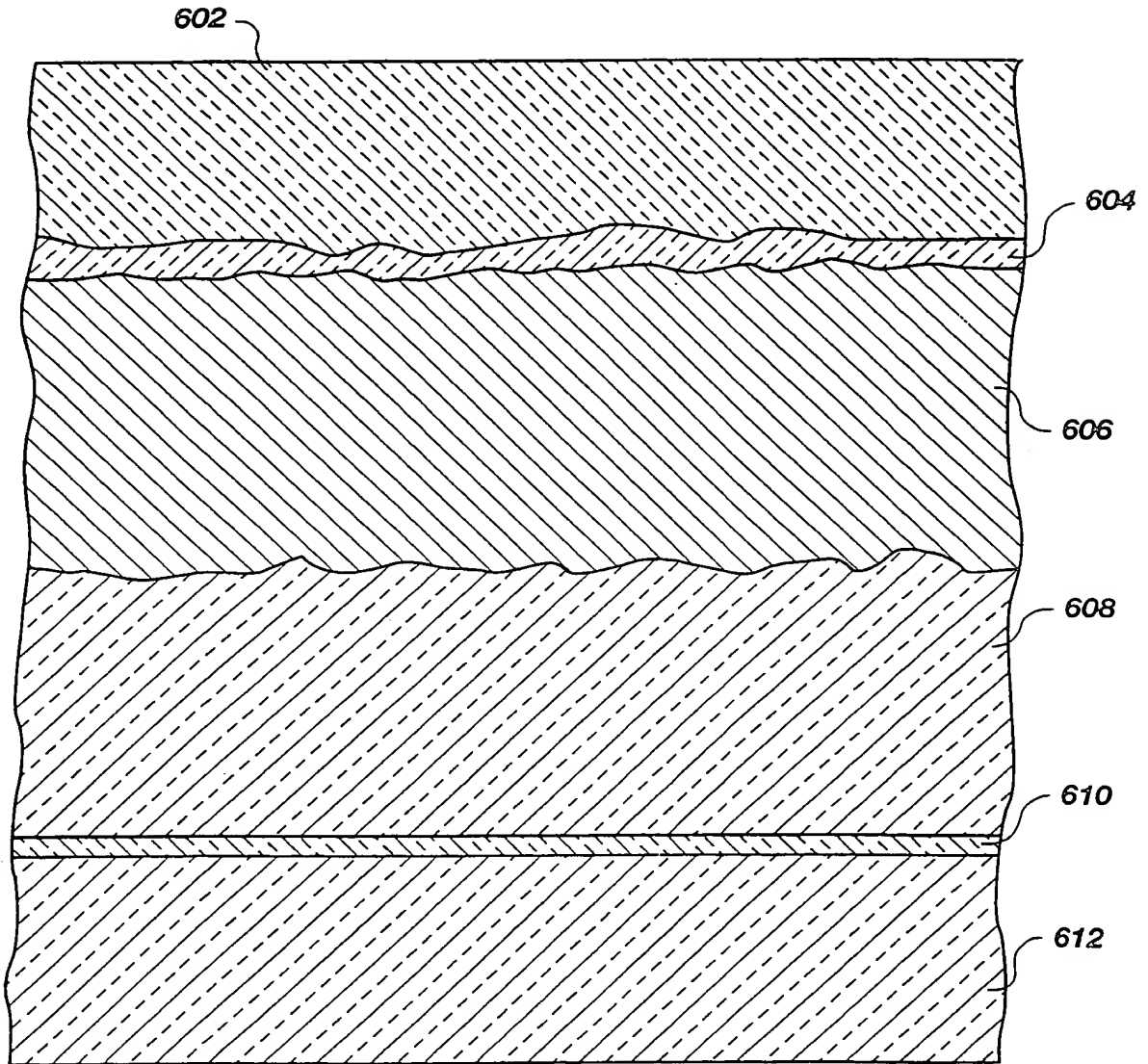


Fig. 24